

A B S T R A C T

A cleaning solution is used to remove a byproduct derived from a decomposed substance of a process gas containing C and F. The cleaning solution contains
5 75 wt% N-methyl-2-pyrrolidone, 15 wt% ethylene glycol monobutyl ether, 0.5 wt% surfactant, and 9.5 wt% water. The content of an alkali metal in the cleaning solution is set to be less than 10 ppb.